



Crystalline silicon mirrors

Substrate and Coating Requirements

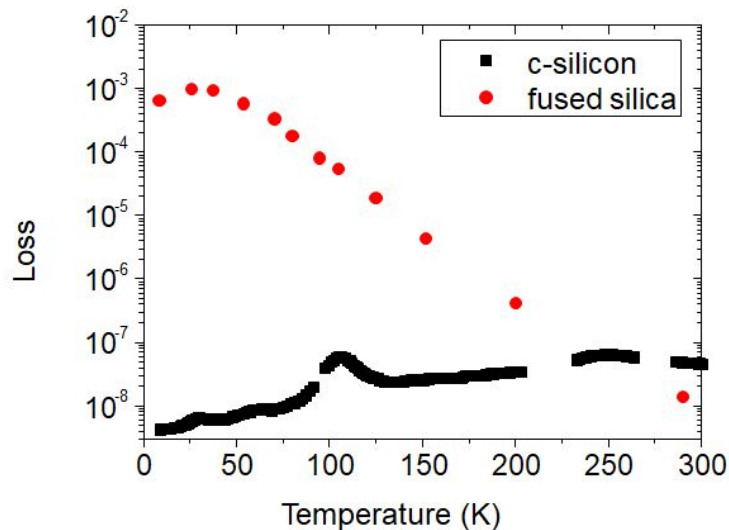
J. Steinlechner 28th Feb 2024

Silicon Substrates

- mass: $\sim 200\text{kg}$ $\rightarrow$ motivated by IFO noise reduction
- diameter: 50cm $\rightarrow$ motivated by coating thermal noise reduction;
 - larger beam diameter reduces coating thermal noise;
 - even if we had extremely good coatings:
minimum mirror diameter, due to laser beam propagation in long ET arms: $35 - 40\text{ cm}$

$\rightarrow$ Very large silicon blocks are required.

- requires very low mechanical loss (high Q-factor)
 - uncritical for monocrystalline material
- requires very low optical absorption at $1550\text{nm}/2000\text{nm}$



data from Jena; published as $1/Q$ in [\[link\]](#)

Silicon: Absorption

- Float zone silicon (undoped):
 - Very pure - optical absorption can be as low as few ppm/cm ✓
 - Drawback: maximum diameter ~20cm ✗
- Czochralski silicon:
 - Diameter up to 45cm (larger in principle possible) ✓
 - Significant impurities, absorption of several thousand ppm/cm or more ✗
- Magnetically purified Czochralski silicon:
 - Can have low absorption similar to float zone material ✓
 - Can in principle be produced with same diameter as standard Czochralski ?
 - Large substrates currently not available ✗
- Directional solidification
 - Very large diameter/mass available ✓
 - Significant impurities ✗

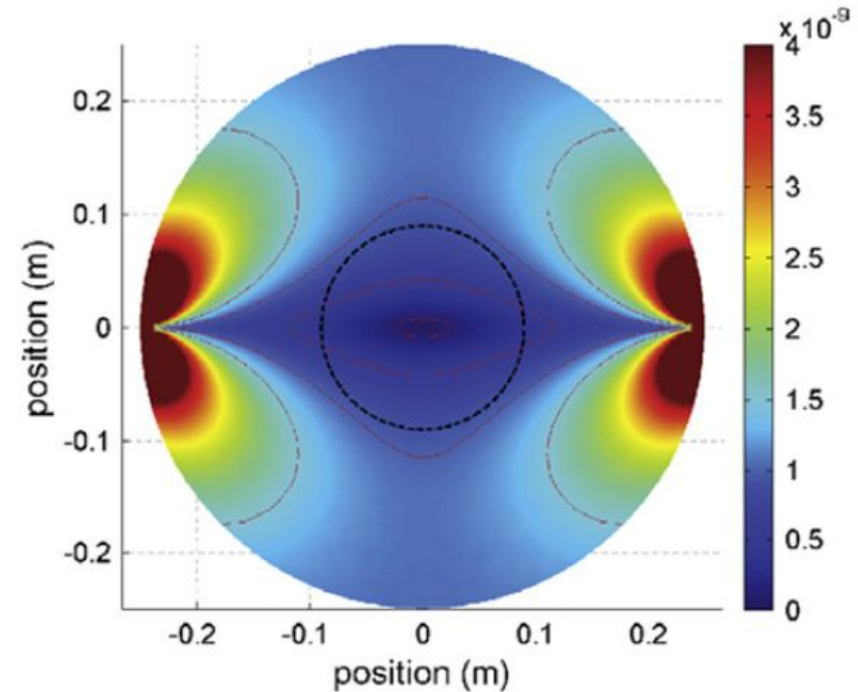
Absorption requirement:
'not as good as FZ, but
much better than standard
Czochralski'

Other considerations:

- Composite test masses?
- Different ITM/ETM material (at different mirror size)?

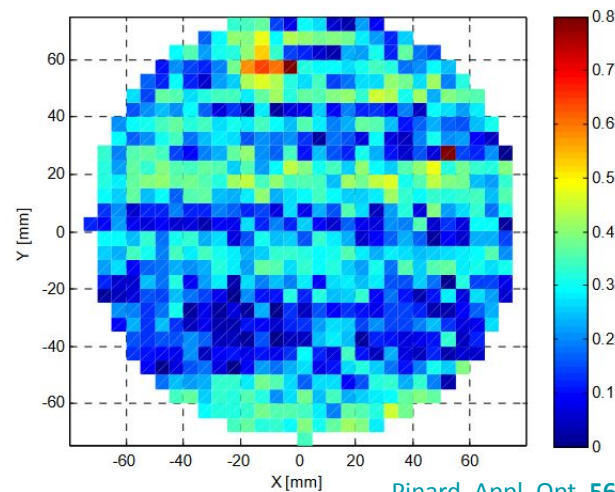
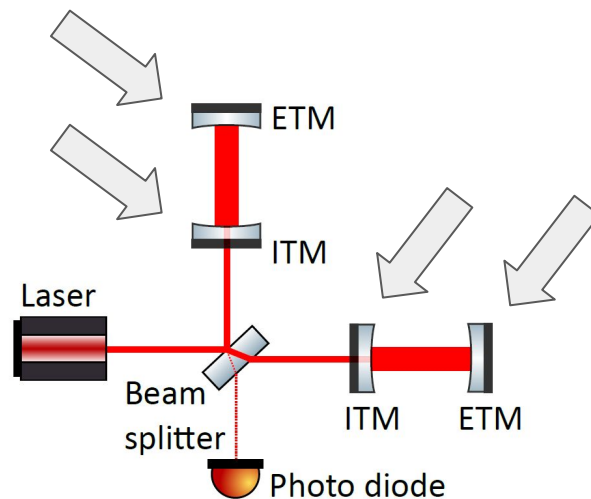
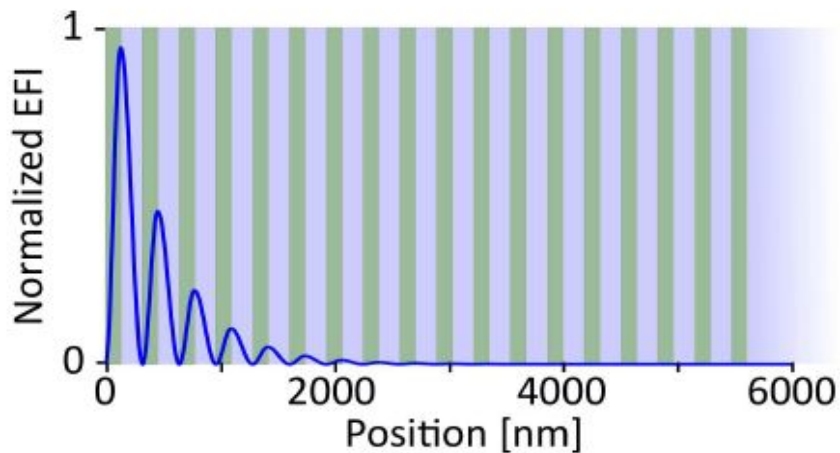
Silicon: Birefringence and other properties

- growth, suspension and heat treatment (required for coating optimisation) lead to internal stresses such as birefringence
- heat treatment: activation of free carriers → absorption increase
- surface absorption: can arise from polishing
- also important: thermal expansion coefficient, homogeneous refractive index, ...

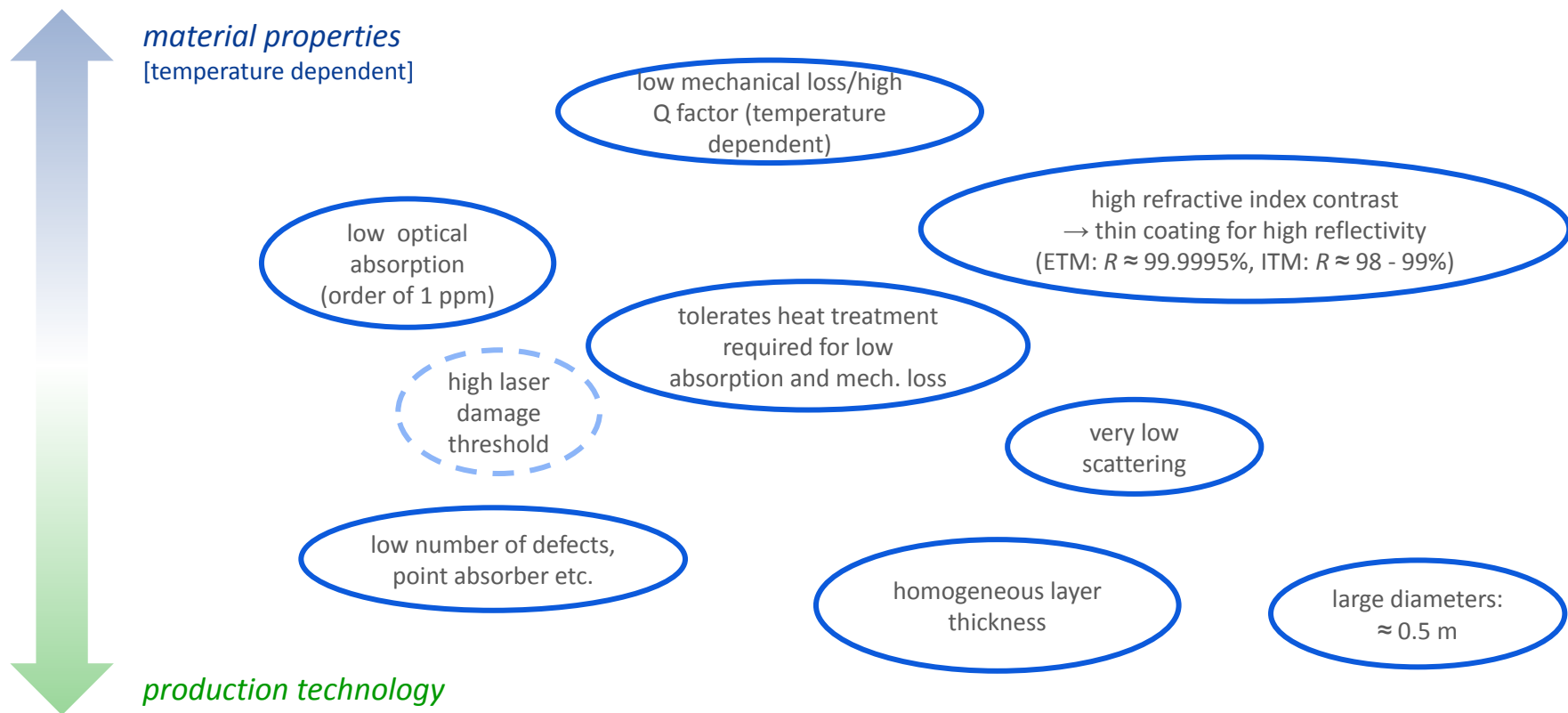


Coatings

- high reflectivity (at 1550nm)
 - ETM $\rightarrow$ 99.9995%
 - ITM $\rightarrow$ 99.9%
- ~ 40 layers or more for ETMs
(depending on refractive index contrast)
- total optical absorption of ~ 1 ppm



Coatings: Further requirements



Coating Options and Materials

- Current coatings made of $\text{SiO}_2/\text{Ta}_2\text{O}_5$
 - mechanical loss increases at low temperatures planned for ET-LF
 - usually heat treated to $\sim 500^\circ\text{C}$ to minimize absorption and mechanical loss
- Of interest at 1550nm and low temperature:
 - a-Si - absorption reduction required
 - SiN - combination with a-Si being explored
 - $\text{SiO}_2:\text{HfO}_2$ - early development phase
 - TiO_2 - crystallizes easily during heat treatment
 - ...
- Other coating concepts
 - monocrystalline multilayers (e.g. [AlGaAs](#))
 - crystalline/amorphous hybrid coatings (e.g. [crystalline toplayer](#))
 - combination of more than two materials in a multilayer stack ([Multimaterial coatings](#))
 - [nanolayers](#) (to suppress crystallisation)
 - ion implantation of reflective layers
 - ...

What the ET Coatings Community can do

Measurements of:

- Optical absorption
 - usually on fused silica substrates, 1" in diameter
- Mechanical loss
 - Room temperature: usually on fused silica substrates, 2 or 3" in diameter, 1mm thick
 - Cryogenics: silicon or sapphire samples, 2" in diameter, between 1 and 5mm thick
- Spectrophotometry: refractive index and thickness needed to analyse mechanical loss and absorption
- Various cycles of heat treatments

→ characterisation of samples can take weeks to months (depending on what we want to know/optimize)

